



PRESS RELEASE  
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## Picosun and Vaisala have worked together in ALD process integration to high volume manufacturing

**HELSINKI UNIVERSITY OF TECHNOLOGY CAMPUS IN ESPOO and VAISALA HQ IN VANTAA, Finland, January 29, 2009** –Leading Atomic Layer Deposition (ALD) systems manufacturer Picosun Oy, Finland, and Vaisala Oyj, Finland-based global market leader in meteorological measurements technology announced today that since 2006 they have worked together for integration of ALD process to high volume manufacturing (HVM). Vaisala has been using Picosun SUNALE™ P-series reactor since late 2006 and began its use in HVM in the early summer of 2007.

Vaisala, global market leader in many of its core businesses, develops, manufactures and markets products and services for environmental and industrial measurement. The major customer groups of Vaisala are meteorological and hydrological institutes, aviation organizations, defense forces, road and rail organizations, weather

related private sector, system integrators and industry worldwide.

"We are extremely proud that Vaisala has chosen Picosun as their ALD tool provider. We are more than happy to announce the exceptional results they have been able to gather since 2006. The ALD process performance in high volume manufacturing, including film uniformity, particles and repeatability, has consistently met the expectations. Our co-operation with Vaisala will lead to new results in implementation of ALD in production, and further strengthen the market position of our SUNALE™ ALD process production tools", says Juhana Kostamo, Managing Director of Picosun Oy.

"We have been satisfied with the results got with Picosun's ALD-reactor. For us easy maintenance, use of commercial standard parts, batch process capability and good reliability were important when we chose our ALD production tool ", says Dr. Antti Rahtu, Manufacturing Manager of Vaisala Oyj.

Picosun is an international equipment manufacturer with world-wide sales and service organization. Picosun develops and manufactures Atomic Layer Deposition (ALD) reactors for micro- and nanotechnology applications. Picosun represents continuity to over three decades of ALD reactor manufacturing in Finland. Picosun provides its customers with versatile, reliable and user-friendly ALD process tools, which offer unique scalability from research to production. Picosun is based in Espoo, Finland and has its US headquarters in Detroit, Michigan. SUNALE™ ALD process tools are installed in various universities, research institutes and companies across Europe, USA and Asia.

Dr Tuomo Suntola, inventor of ALD technology, is Member of the Board of Directors of Picosun. World's most experienced ALD reactor designer Sven Lindfors is Picosun's Chief Technology Officer and one of the founders of the company. Picosun Oy is a part of Stephen Industries Inc Oy.

### EXCEPTIONAL RESULTS REPORTED BY VAISALA

Measured data by Vaisala Oyj using Picosun's SUNALE™ ALD reactor

#### FILM

UNIFORMITY	Specification	Measured data
Within Wafer	< 1.0 %	0.6 %
Within Batch	< 2.0 %	1.0 %
Batch to Batch	< 2.0 %	0.3 %

#### Additional Information:

##### **Picosun Oy, Mr. Juhana Kostamo, Managing Director**

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##### **Vaisala Oyj, Dr. Antti Rahtu, Manufacturing Manager**

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